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## **Entegris Extends Its VaporSorb(TM) Filter Line for Advanced Yield Protection in Semiconductor Processing**

### **New Filter Provides Total Acid Removal From Environmental Air in Chemical Mechanical Planarization (CMP) Process Tools**

BILLERICA, Mass., Oct. 21, 2014 (GLOBE NEWSWIRE) -- Entegris, Inc. (Nasdaq:ENTG), a leader in yield-enhancing materials and solutions for highly advanced manufacturing environments, today announced a new product for its VaporSorb™ line of airborne molecular contamination (AMC) filters. The new filter was created as an "all-in-one," single-filter solution for capturing critical AMC in the chemical mechanical planarization process, or CMP, in semiconductor manufacturing. VaporSorb, which is a leading brand of filter used in cleanroom environments and for process tools during key steps in manufacturing, is the first such filter available for CMP process tools that protects against weak acids as well as other contaminants.

The new filter was designed specifically for CMP tools to provide balanced lifetimes for all critical AMC in a single filter which avoids the complexities of multi-filter handling. In addition, the filter retains the VaporSorb brand's industry-leading service life to reduce both tool downtime and cost of ownership.

"Yield concerns in the CMP process, just as in the photolithography process, can be addressed by providing complete AMC protection. This means protecting against weak acids, as well as strong acids and other contaminants," stated Entegris Product Marketing Manager for AMC Filtration Solutions, Marc Venet. "With VaporSorb CMP, we have a single solution that completely addresses AMC-induced corrosion defects in CMP processes."

Examples of weak acids include acetic and formic acids (acetate;  $\text{CH}_3\text{COO}^-$  and formate;  $\text{HCOO}^-$ ) and nitrous acid (nitrite;  $\text{NO}_2^-$ ). Strong acids include  $\text{HNO}_3$ ,  $\text{SO}_2$ ,  $\text{H}_2\text{SO}_4$  and  $\text{HCl}$ . These contaminants are causing concerns regarding defects and yield in CMP processes.

In July, the company launched the industry's first "four-in-one" filter, the VaporSorb TRK for photolithography tools, to capture airborne organics, bases, strong acids and weak acids. VaporSorb filters use Entegris' own unique mix of materials to capture airborne molecular contaminants, which are tailored to create application- and fab-specific filter solutions.

For more information about VaporSorb CMP filters, go to [www.entegris.com](http://www.entegris.com).

### **About Entegris**

Entegris is a leading provider of yield-enhancing materials and solutions for advanced manufacturing processes in the semiconductor and other high-technology industries. On April 30, 2014, Entegris acquired Danbury, CT-based ATMI, Inc. Entegris is ISO 9001 certified and has manufacturing, customer service and/or research facilities in the United States, China, France, Germany, Israel, Japan, Malaysia, Singapore, South Korea and Taiwan. Additional information can be found at [www.entegris.com](http://www.entegris.com).

CONTACT: Andrew DePoy

Brand & Marcom Mgr.

T +1 602 220 4341

[andrew\\_depoy@entegris.com](mailto:andrew_depoy@entegris.com)

Media Contact:

Lora Martinez

Impress Labs

303.941.6110

[lora@impresslabs.com](mailto:lora@impresslabs.com)